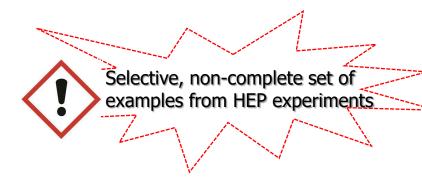


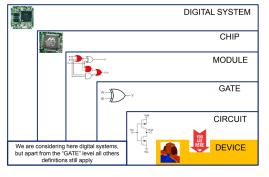
## Outline

- Motivation & Challenges
- Device-level & Mixed mode simulations
  - > Radiation damage effects models
  - Next generation silicon detectors
  - Rad-Hard and innovative materials
- Combine TCAD and AllPix Squared
- Conclusions

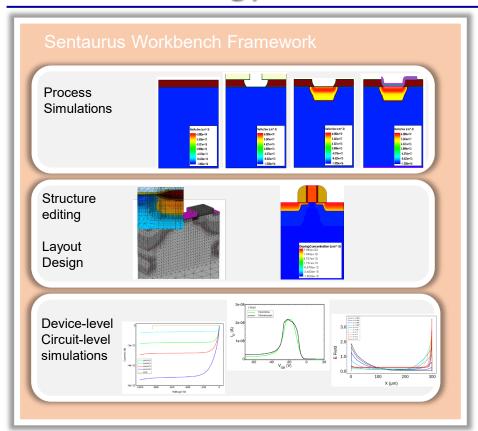


## Motivations and Challenges

- □ Performance of complex sensors is not analytically predictable anymore!
  - → Increasing need for TCAD simulations.
- ☐ Semiconductor detectors will face increasing radiation levels
  - $\sim$  >1x10<sup>16</sup> 1MeV n<sub>ea</sub>/cm<sup>2</sup> (HL-LHC);
  - $>5x10^{17} 1 \text{MeV n}_{eq}/\text{cm}^2 (FCC-\text{hh});$ 
    - detectors used at LHC cannot be operated after such irradiation.
- New requirements lead to new detector technologies
  - Need to be optimized for radiation hardness and/or 4D tracking capabilities.
- Modern TCAD simulation tools can have a crucial role in radiation-hard device design
  - Reducing costly and time-consuming physical testing.
  - ☐ To get insights. Deep understanding of physical device behavior.
  - ☐ To quickly screen technological options and drive the industrial strategy.
  - ☐ Combined Bulk and surface radiation damage can be considered.
  - ☐ Within a hierarchical approach, increasingly complex models can be considered, by balancing complexity and comprehensiveness.



## The Technology-CAD modeling approach



- √ TCAD simulation tools solve fundamental, physical partial differential equations, such as diffusion and transport equations for discretized geometries (finite element meshing).
- √ This deep physical approach gives TCAD simulation predictive accuracy.
- ✓ Synopsys<sup>©</sup> Sentaurus TCAD

 $\vec{J}_{p} = -q\mu_{p}p\nabla\varphi - qD_{p}\nabla p$ 

# Radiation damage models

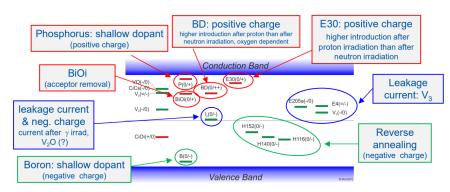
Synopsys Sentaurus TCAD Sdevice simulations for HEP experiments

## TCAD models - an overview

#### Different approaches to TCAD radiation damage modeling:

- ✓ <u>EVL Model</u> (2 levels)
- ✓ <u>Delhi-2014</u> (2 levels)
- $\checkmark$  KIT (Eber) (2 levels)
- ✓ New Univ. Of Perugia Bulk+Surface (3 levels)
- ✓ Folkestad (CERN model)/LHCb (3 levels)
- ✓ Hamburg Penta Trap Model (HPTM) (5 levels)

Different modeling approaches (traps, energy levels and related parameters), often tailored to specific datasets and devices.



RD50 map of most relevant defects for device performance near RT

#### GOAL: General purpose TCAD model (DRD3 WP4 - ECFA Detector R&D Roadmap)

- Not over specific
  - → set of "effective" defects within the semiconductor bandgap.
- Predictive capabilities to be extended  $\Phi > 10^{16} \text{ n}_{eq}/\text{cm}^2$ .
- Accounts for different irradiation levels and particle types.

## Hamburg Penta Trap Model (HPTM)

- HPTM with 5 effective traps
  - Developed to simulate the I-V, C-V and CCE with IR of diodes for various fluence levels and use the TCAD optimizer to determine the free parameters i.e., minimize simultaneously for every fluence.
- Optimize the performance of pad diodes irradiated with 24 GeV/c p in the fluence range of  $3 \cdot 10^{14}$  to  $1.3 \cdot 10^{16}$  n<sub>ea</sub>/cm<sup>-2</sup>.
- Charge trapping is essential to predict the response of radiation-damaged segmented sensors, due to the highly non-uniform weighting field.

## H220

Defect

E30K

$C_i O_i$	Donor	EV+0.36 eV	0.5780	3.230E-17	2.030E-14	
• Trap	concentrati	on of defects: <b>N</b> :	= g <sub>int</sub> · Φ <sub>neq</sub>			

 $g_{int}$ 

 $[cm^{-1}]$ 

0.0497

 $[cm^2]$ 

2.300E-14

2.551E-14

4.478E-15

[cm<sup>2</sup>]

2.920E-16

1.511E-13

 Simulations for the optimization have been performed at T= -20 °C with: 1. Slotboom band gap narrowing

Donor

Result of tuning: Hamburg Penta Trap Model (HPTM)

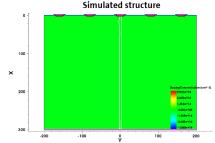
Energy

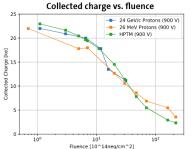
 $E_C$ -0.1 eV

Ec-0.458 eV

- 2. Impact ionisation (van Overstaeten-de Man)
- 3. Trap Assisted Tunneling Hurkx with tunnel mass = 0.25 m. (default value: 0.5 m<sub>e</sub>) in case of the I<sub>p</sub>
- 4. Relative permittivity of silicon = 11.9 (default value: 11.7)
- Both cross section for the E30K and the electron cross section for the C<sub>i</sub>O<sub>i</sub> were fixed → 12 free parameter
- Optimization done with the nonlinear simplex method







- Float zone silicon
- 300 um thick sensors
- 80 um pitch
- T = -25 °C
- 90Sr source

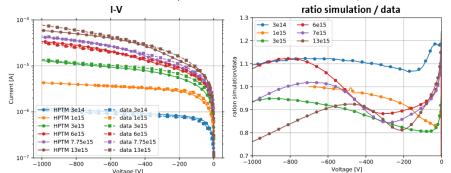
Data from A. Affolder et al., NIMA Vol. 623 (2010), pp. 177-179.

- J. Schwandt, arXiv:1904.10234.
- J. Schwandt, IEEE NSS MIC 2028 talk.

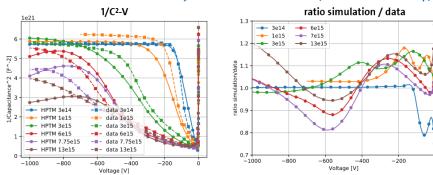


## **HPTM Simulation results**

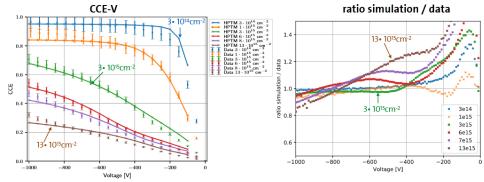
#### I-V for fluences from 0.3 - 13•1015 n<sub>eq</sub>/cm<sup>2</sup> at T= -20 °C (for T= -30 °C see backup)



#### C-V for fluences from 0.3 - 13•10<sup>15</sup> n<sub>eq</sub>/cm<sup>2</sup> at 455 Hz and T = -20 °C (for T= -30 °C see backup)



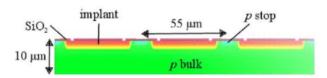
## CCE vs. V for fluences from 0.3 - $13 \cdot 10^{15} \, n_{eq}/cm^2$ with infrared laser and T = -20 °C (for T= -30 °C see backup)



T= -20°C, 60min at 80°C

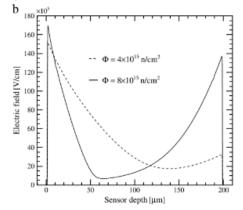
- J. Schwandt, arXiv:1904.10234.
- J. Schwandt, IEEE NSS MIC 2028 talk.

# CERN bulk radiation damage model (Folkestad)

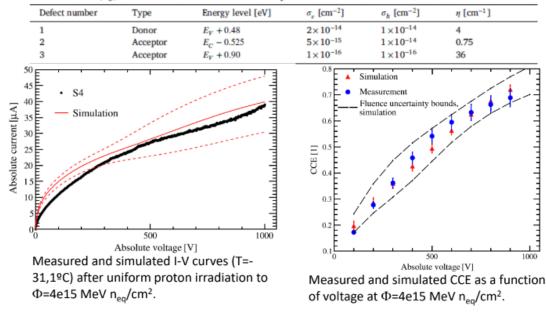


From the classical **EVL model\***, one donor and one acceptor level (1 and 2 in the table), they add a third acceptor level. Cross-sections are adjusted to experimental results. Measurements for 200  $\mu$ m thick n-on-p sensors bump bonded to TimePix3 readout .

Simulated electric field (2D mesh) in pixel centre at 1000V bias for two fluence levels.

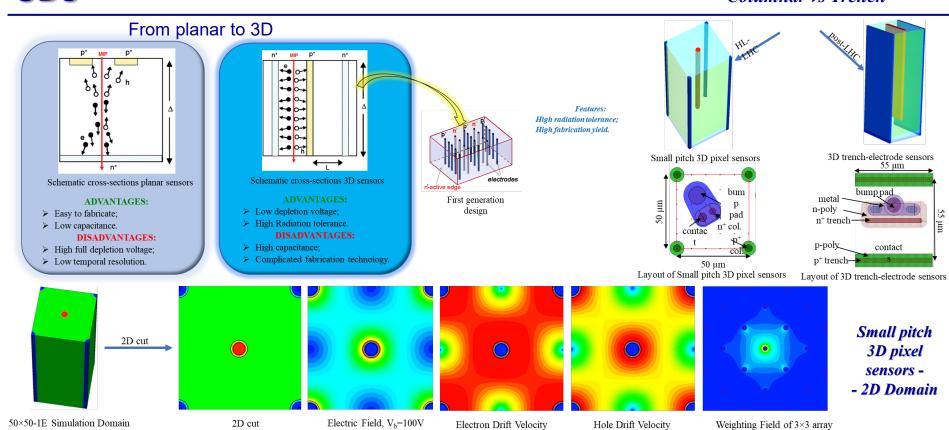


A. Folkestad et al., NIM A 874 (2017) pp. 94-102 F.R. Palomo, VERTEX2019 Parameters of the proposed radiation damage model. The energy levels are given with respect to the valence band  $(E_V)$  or the conduction band  $(E_C)$ . The model is intended to be used in conjunction with the Van Overstraeten–De Man avalanche model.



The model captures the transition from a linear electric field/saturating I-V curve to a double junction electric field/non-saturating I-V curve, as a consequence of avalanche generation in the high-field regions of doublé junctions. For pixel center hit, the CCE is aceptable.

#### Columnar vs Trench



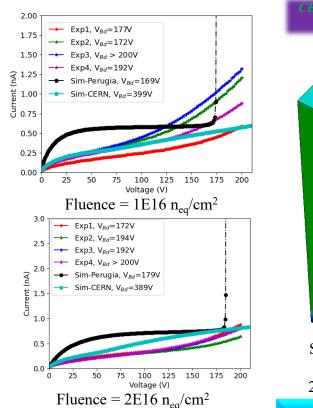
 $V_{b} = 100 V$ 

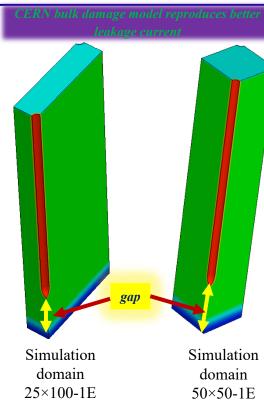
 $V_b=100V$ 

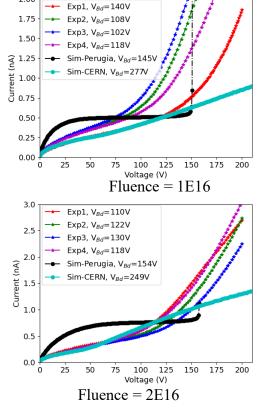
Material courtesy of G.-F. Dalla Betta

10

## Small pitch 3D pixel sensors – 3D Domain







Perugia bulk damage model is better at predicting the breakdown voltage

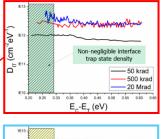
Material courtesy of G.-F. Dalla Betta

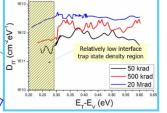


# The "New Univ. of Perugia" model - at a glance



Туре	Energy (eV)	Band width (eV)	Conc. (cm <sup>-2</sup> )
Acceptor	$E_C \le E_T \le E_C - 0.56$	0.56	$D_{IT} = D_{IT}(\Phi)$
Donor	$E_V \le E_T \le E_V + 0.6$	0.60	$D_{IT} = D_{IT}(\Phi)$

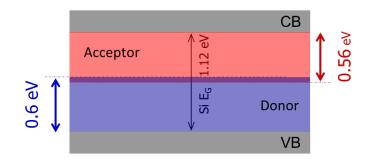


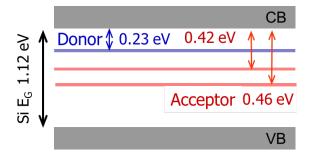


### √ Bulk damage

Туре	Energy (eV)	η (cm <sup>-1</sup> )	σ <sub>n</sub> (cm²)	σ <sub>h</sub> (cm <sup>2</sup> )
Donor	E <sub>c</sub> - 0.23	0.006	2.3×10 <sup>-14</sup>	2.3×10 <sup>-15</sup>
Acceptor	E <sub>c</sub> - 0.42	1.6	1×10 <sup>-15</sup>	1×10 <sup>-14</sup>
Acceptor	E <sub>C</sub> - 0.46	0.9	7×10 <sup>-14</sup>	7×10 <sup>-13</sup>



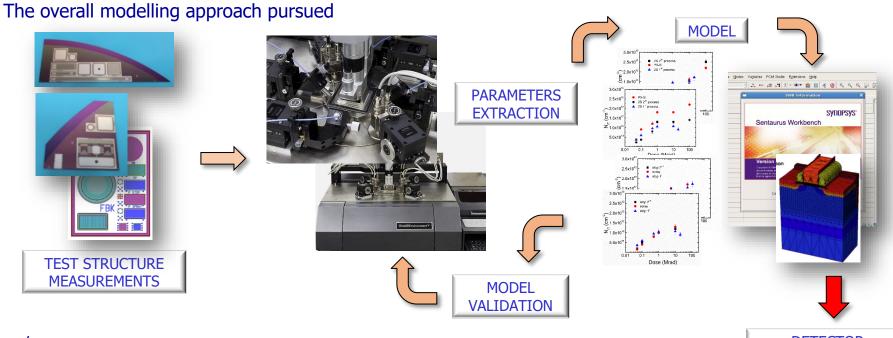




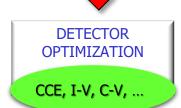
A. Morozzi et al., Front. Phys., 9 (2021)



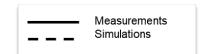
# The "New Univ. of Perugia" model – flow

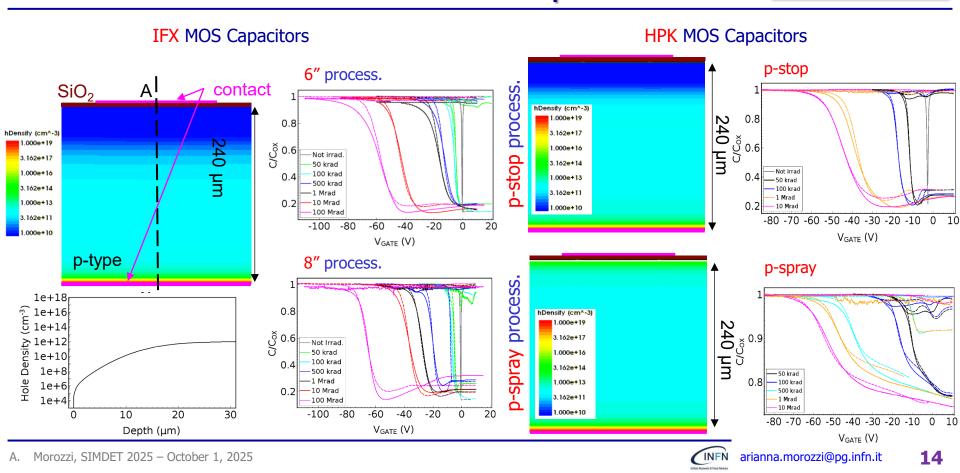


- $\checkmark$  Modeling the effects of the radiation damage.
- $\sqrt{\mbox{ Predictive insight}}$  into the behavior of detectors, aiming at their performance optimization.

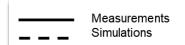


# Surface model validation: MOS capacitors

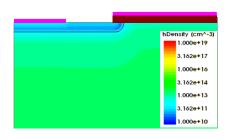




## Surface & Bulk model validation

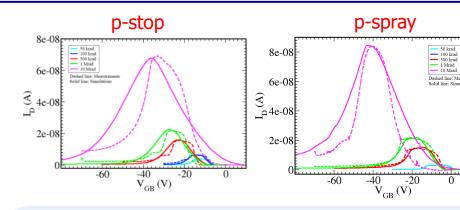


#### **HPK** Gated Diodes

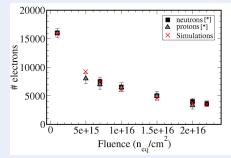


- $\checkmark$  I-V characteristics as a function of  $V_{\text{GATE}}$ .
- ✓ From I-V measurements the surface velocity s<sub>0</sub> was evaluated as a function of the dose.

$$s_0 = \frac{\pi}{2} \sigma_s v_{th} D_{it} k_B T \quad s_0 = \frac{I_s}{n_i q A_G}$$

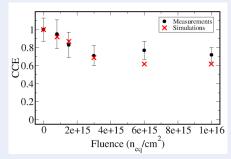


#### Charge Collection for silicon strips.



[\*] A. Affolder et al., NIMA Vol. 623 (2010), pp. 177-179.

#### Charge Collection for PiN diodes.



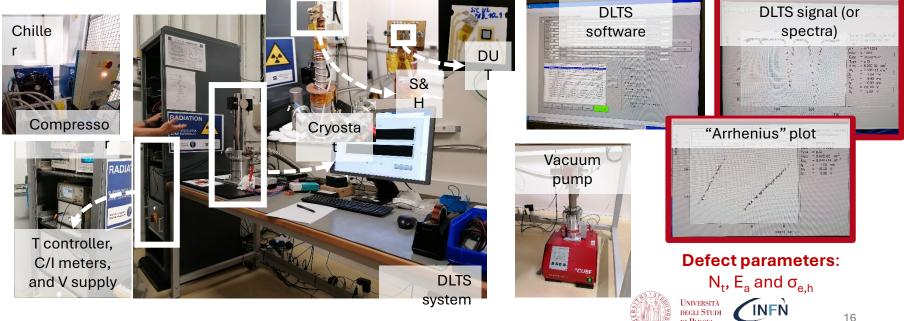
F. Moscatelli et al., IEEE TNS 64(8) (2017), pp. 2259 – 2267.

Data from M. Ferrero, 34th RD50 Workshop (2019)



# Deep Level Transient Spectroscopy

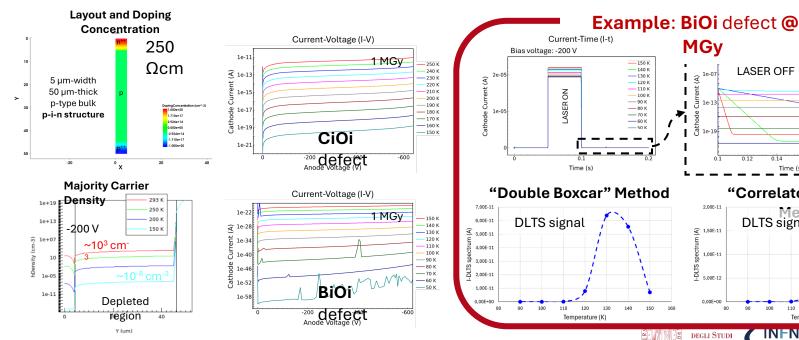
• **Defect spectroscopy**: setup, training and measurements at Deep Level Transient Spectroscopy (**DLTS**) system – SSD Lab, CERN EP-DT group (April-September '25).

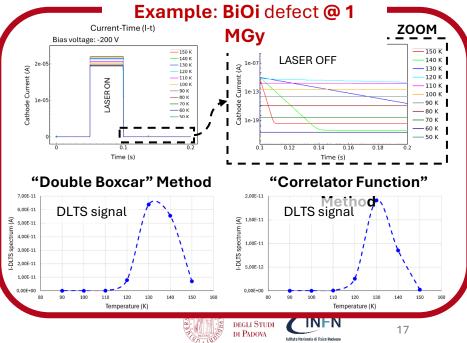


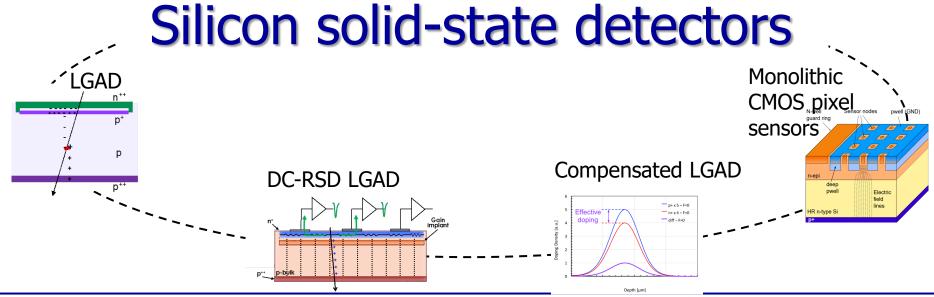


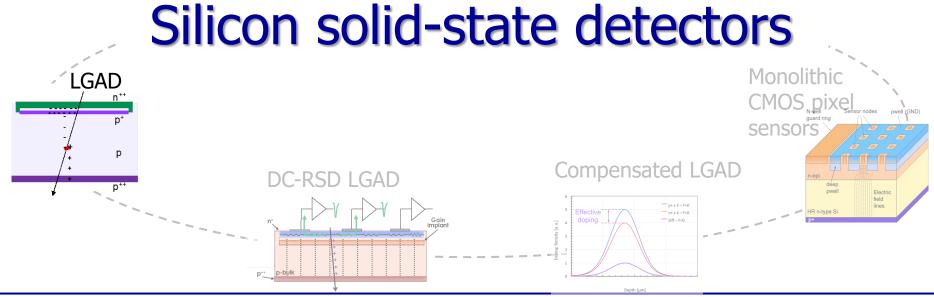
# Deep Level Transient Spectroscopy: TCAD approach

• Development of a TCAD simulation framework capable of reproducing **DLTS** measurement results – SSD Lab, CERN EP-DT group (April-September '25).









## Low Gain Avalanche Diodes

This work has been supported by the Italian PRIN MIUR 2017 "4DInsibe" under GA No 2017L2XKTJ, by the European Union's Horizon 2020 Research and Innovation programme under GA No 101004761 "eXFlu-innova" and it has been conducted in collaboration with the INFN CSN5 "eXFlu" research project.

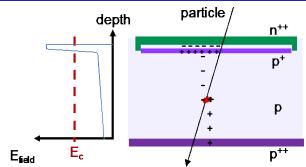




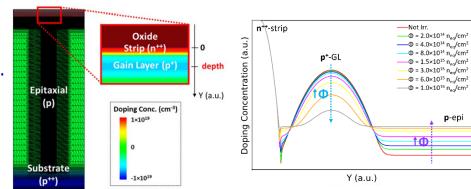
- n-in-p silicon sensors
- Operated in **low-gain regime** (20 30)
- Critical electric field ~ 20 30 V/μm
- Good candidates for 4D tracking
- Mitigation of the radiation damage effects by exploiting the controlled charge multiplication mechanism.

#### Advanced TCAD modeling

- Radiation damage effects model implementation
- Accounts for the acceptor removal mechanism<sup>[5]</sup> which deactivates the p<sup>+</sup>-doping of the gain layer with irradiation.
- Electrical behavior prediction/ performance optimization up to the highest fluences.



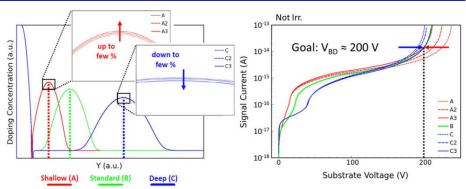
#### Layout and doping profile

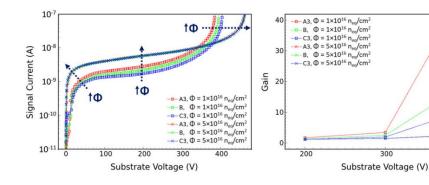


M. Ferrero et al., doi:10.1016/j.nima.2018.11.121 T. Croci et al 2022 JINST 17 C01022

# Gain layer sensitivity analysis

- Three different doping profiles considered
  - Shallow, Standard, Deep.
  - **Gain layer** peak: a variation of a few percentages affects the breakdown voltage (V<sub>RD</sub>).
  - Effect on the gain layer depletion voltage.
  - **Predictive** analysis on sensor performance considering the radiation damage effects.





T. Croci et al 2023 JINST 18 C01008.



400

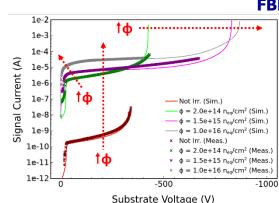
This work has been supported by the Italian PRIN MIUR 2017 "4DInSiDe" under GA No 2017L2XKTJ, by the European Union's Horizon 2020 Research and Innovation programme under GA No 101004761 "eXFlu-innova" and it has been

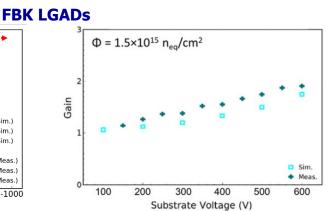




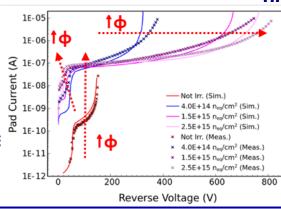


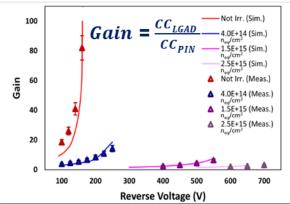
- 55 µm thick
- **HPK LGADs** (HPK2, split 1-2)
  - 50 μm thick
- Simulations-Measurements comparison for not irradiated and irradiated devices.
- TCAD settings:
  - "PerugiaModDoping"
  - Massey avalanche model (FBK) and vanOverstraeten-de Man (HPK).
  - Temperature sets as per experimenta measurements (RT not irrad, 248 K irrad).



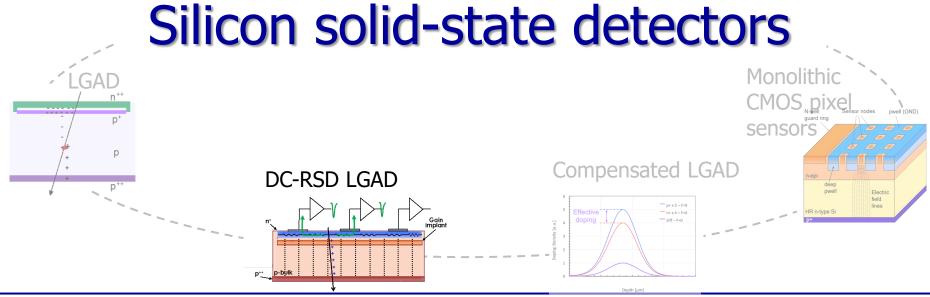








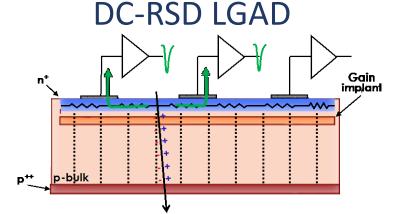




# Resistive Silicon Detectors (RSDs)

# AC-RSD LGAD Coupling dielectric graph of the coupling dielectric

- ✓ This design has been manufactured in several productions by FBK, BNL, and HPK.
  - 1. Long-tail bipolar signals
  - Baseline fluctuation
  - 3. Uncontrolled signal spreading
  - 4. Not easily scalable to large-area sensors



- ✓ Design actually under development by FBK.
- ✓ Promising solution for 4D tracking.
  - 1. Unipolar signals
  - Absence of baseline fluctuation
  - 3. Controlled signal spread
  - 4. Large sensitive areas
- ✓ Evaluation of different layouts and technologies for future DC-RSD production using TCAD tools;

R. Arcidiacono et al., NIM A 1057 (2023), 168671



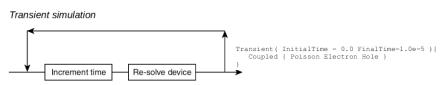
# Heavy Ion model description

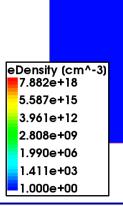
Transient time simulation to study the active behavior of detectors.

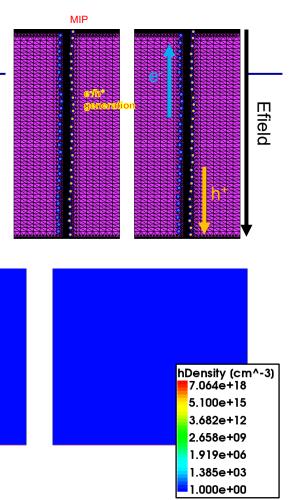
□ HeavyIon model.

```
Heavylon(
Time = 1e-9
Location =(0,0)
Direction =(0,1)
Let_f = @LET_f_pC@
Length = 60
Wt_hi = 0.25
Picocoulomb)
```

After the heavy ion impinges the device across a specified particle path, electron-hole pairs are generated and by means of drift-diffusion mechanisms reach the collect contacts.

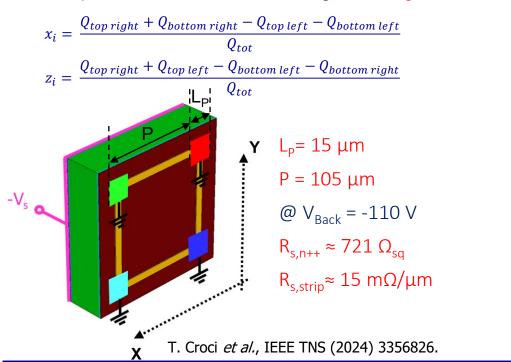




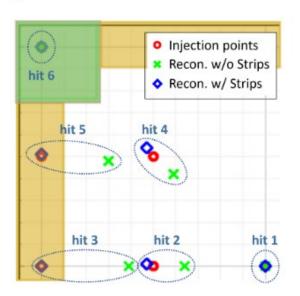


## Reconstruction

- Stimulus MIP (Minumum Ionizing particle)
- The position is reconstructed using the charge imbalance



#### **Results** from *TCAD* simulations

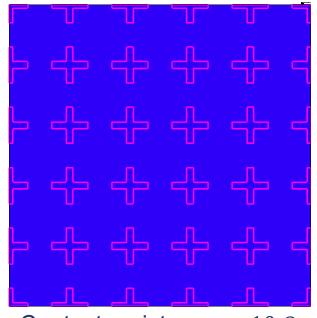


Avalanche model: Massey. Temperature 300 K

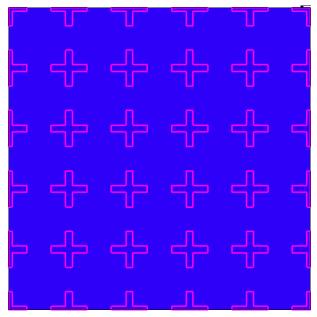
## Investigate the effect of the contact resistance

7-50 TotalCurrentDensity (A\*cm^-2)
6.000e+02
1.506e+02
3.780e+01
9.487e+00
2.381e+00
5.976e-01
1.500e-01

- ☐ Investigation of the signal confinement within the TCAD environment.
- ☐ Minimum Ionizing Particle (MIP): various hit points considered.

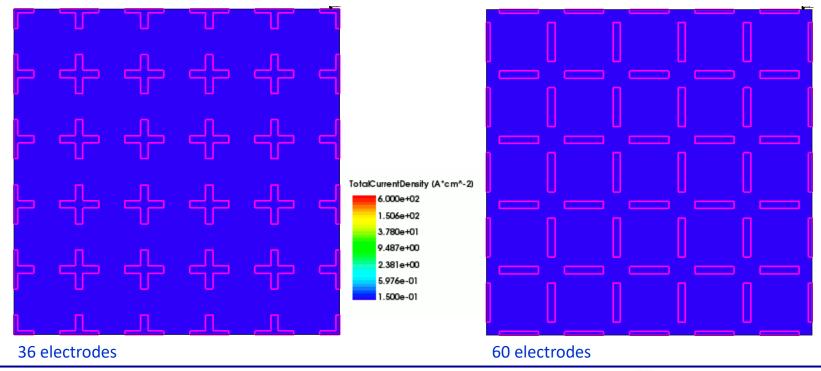


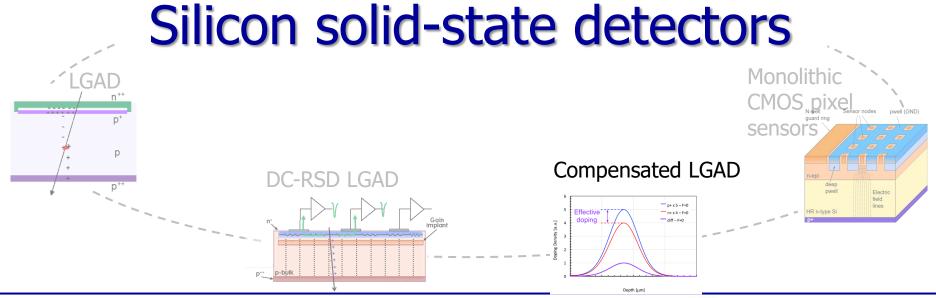
Contact resistance =  $10 \Omega$ 



Contact resistance =  $1 k\Omega$ 

# Investigate the effect of the contact shape



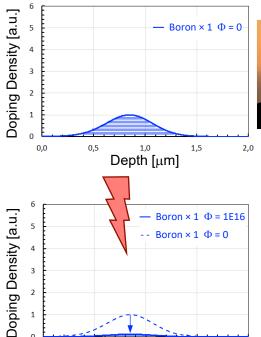


## Compensated LGADs for eXtreme Fluences









Boron  $\times$  1  $\Phi$  = 1E16

1,5

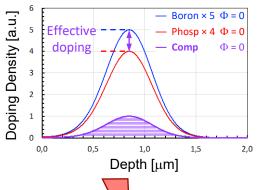
2,0

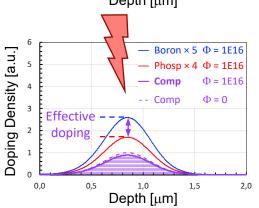
-- Boron  $\times 1 \Phi = 0$ 

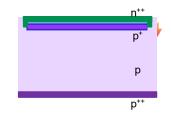


Irradiation  $\Phi = 1 \times 10^{16} / \text{cm}^2$ 

#### **Doping Profile – Compensated LGAD**







Compensated LGAD

Use the interplay between acceptor and donor removal to keep a constant gain layer active doping density

#### Many unknowns:

- □ donor removal coefficient, from  $n^+(\Phi) = n^+(0) \cdot e^{-c_D \Phi}$
- interplay between donor and acceptor removal (c<sub>D</sub> vs c<sub>△</sub>)
- ▶ effects of substrate impurities on the removal coefficients

Material courtesy of V. Sola

Depth [μm]

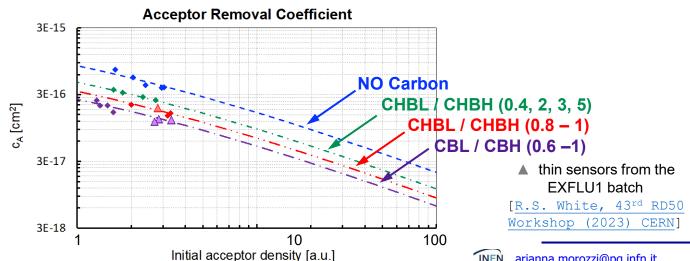
0,0

## Gain Removal Mechanism in LGADs

The acceptor removal mechanism deactivates the p<sup>+</sup>-doping of the gain implant with irradiation as  $p^+(\Phi) = p^+(0) \cdot e^{-cA\Phi}$ 

where  $c_{\Delta}$  is the acceptor removal coefficient and depends on the initial acceptor density, p<sup>+</sup>(0), and on the defect engineering of the gain layer atoms

> To substantially reduce  $c_{\Delta}$ , it is necessary to increase p<sup>+</sup>(0), the initial acceptor density

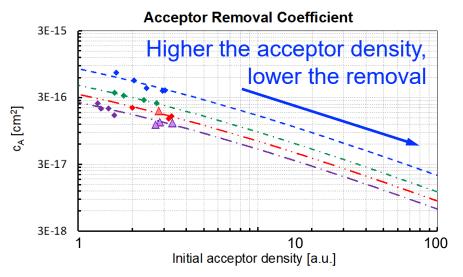


## Gain Removal Mechanism in LGADs

The acceptor removal mechanism deactivates the p<sup>+</sup>-doping of the **gain implant** with irradiation as  $p^+(\Phi) = p^+(0) \cdot e^{-c_A \Phi}$ 

where  $c_A$  is the acceptor removal coefficient and depends on the initial acceptor density,  $p^+(0)$ , and on the defect engineering of the gain layer atoms

To substantially reduce  $c_A$ , it is necessary to increase  $p^+(0)$ , the initial acceptor density



thin sensors from the EXFLU1 batch

[R.S. White, 43rd RD50 Workshop (2023) CERN]



# Investigation of the donor removal

While donor removal has been investigated for doping densities of  $10^{12} - 10^{14}$  cm<sup>-3</sup>, the design of compensated LGADs requires examining the  $10^{15} - 10^{17}$  cm<sup>-3</sup> range, which will be addressed through two different methodologies.

#### Comparison between TCAD simulations and experimental measurements of

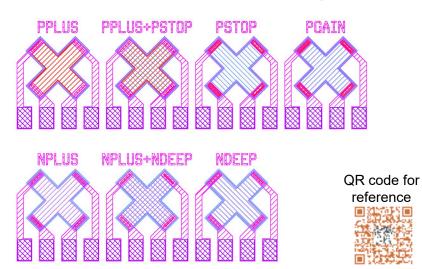
#### compensated LGADs (C-V)

#### EXFLU1's split table

[a < b < c] [2c < 3a]

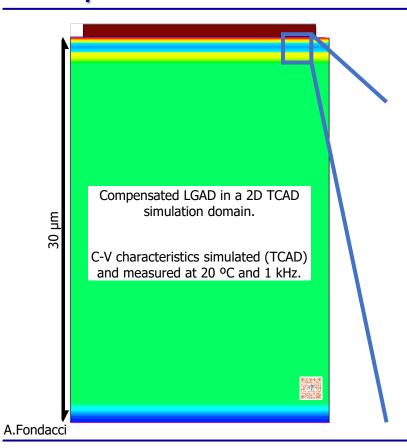
Wafer#	Thickness	p+ dose	n+ dose	C dose
6	30	2 a	1	
7	30	2 b	1	
8	30	2 b	1	
9	30	2 c	1	
10	30	3 a	2	
11	30	3 b	2	
12	30	3 b	2	
13	30	3 b	2	1.0
14	30	3 c	2	
15	30	5 a	4	

#### van der Pauw test structures $(R_{sh})$

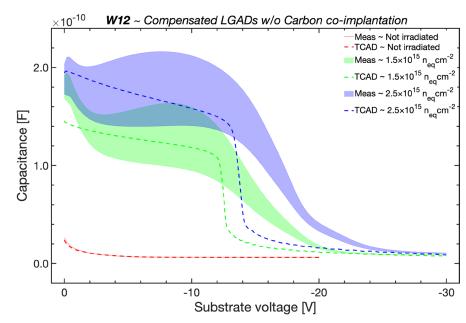


A.Fondacci

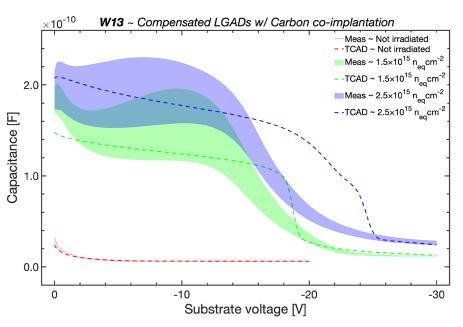
## Compensated LGADs to extract donor removal



## Compensated LGADs to extract donor removal



Exploiting the experimental acceptor removal coefficient  $c_A = 2.50 \cdot 10^{-16} \, cm^2$ , the agreement with C-V measurements is achieved using a donor removal coefficient  $c_D = 6.50 \cdot 10^{-16} \, cm^2$ .



Exploiting the extracted  $c_{D}=6.50\cdot 10^{\cdot 16}~cm^{2}$  and the experimental  $c_{A}=8.26\cdot 10^{\cdot 17}~cm^{2}$  for carbon co-implantation, a good agreement between measurements and simulations was achieved.

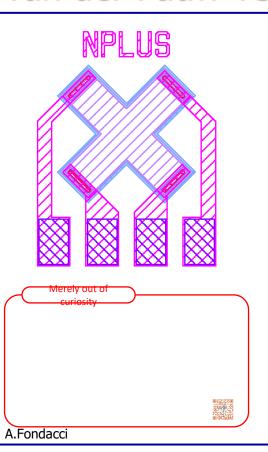
A.Fondacci

## Van der Pauw TS to extract donor removal

Use of the variation in sheet resistance with irradiation to extract and validate donor (and acceptor) removal.



### Van der Pauw TS to extract donor removal

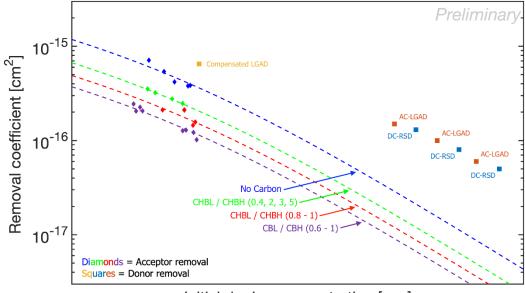




$c_D$ donor removal coefficient values [ $10^{-16}$ cm $^2$ ]				
Location	Irradiation	W3	W6	W14
KIT	Neutron	$1.5 \pm 0.2$	$1.0 \pm 0.2$	$0.6 \pm 0.2$
	Proton	$4.6 \pm 0.4$	$2.9 \pm 0.4$	$1.7 \pm 0.3$
Perugia	Neutron	$1.6 \pm 0.2$	$1.0 \pm 0.2$	$0.7 \pm 0.1$
	Proton	$4.7 \pm 0.6$	$2.9 \pm 0.4$	$1.7 \pm 0.3$

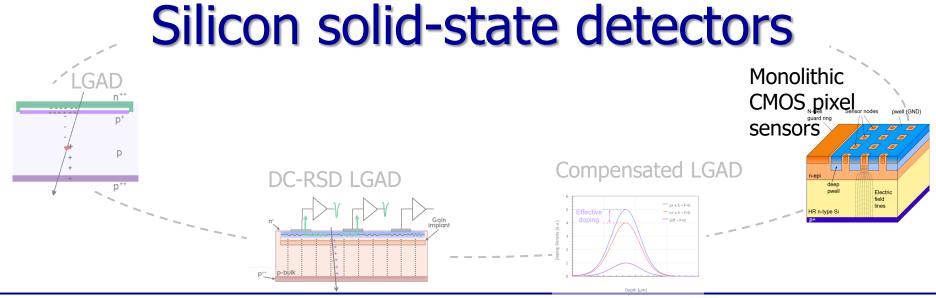
### Taking Stock

- Compensated LGADs aim to extend 4D tracking to the extreme fluences expected at future hadron colliders.
- Their design requires an accurate characterisation of donor removal at high initial donor concentrations (>10<sup>15</sup> cm<sup>-3</sup>).
- To this end, two new strategies have been explored, leading to the following preliminary results:



A.Fondacci

Initial doping concentration [a.u.]

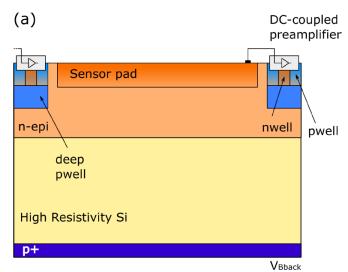


### Monolithic sensors with avalanche gain

Main driver: ALICE 3 ToF layers. Target resolution:

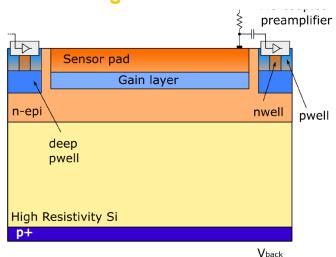
20ps

### **Fully Depleted PAD sensors**



- Sensors can be biased at low voltage
- DC coupling with front-end amplifier is possible

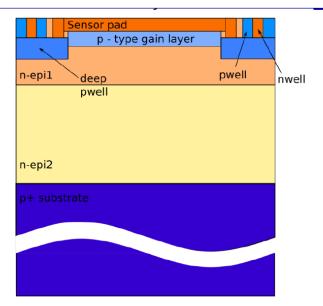
## Fully Depleted PAD sensors with avalanche gain

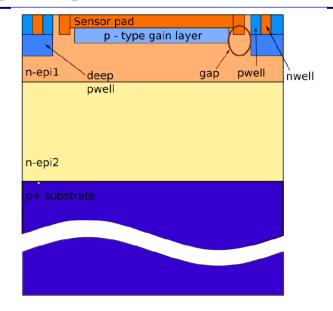


- High voltage is needed on the top side
- AC coupling of front-end amplifier is needed



### Monolithic sensors with avalanche gain: junction termination





#### **Layout A1**

**Termination shielded** by deep pwell: electrons generated below the deep pwell reach the gain layer

#### **Layout A2**

**Termination** directly **facing the active region**: electrons generated below termination can be collected without gain



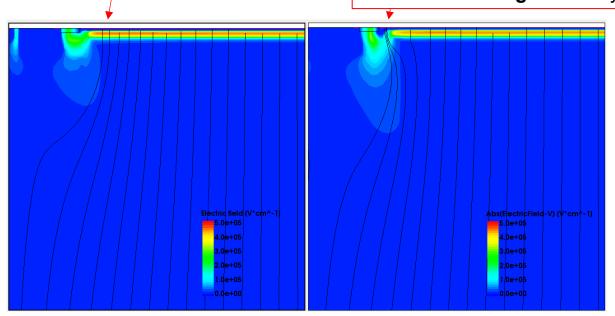
### Monolithic sensors with avalanche gain: electric field lines

All the field lines cross the gain region:

- 100% fill factor
- non-uniform gain and timing

Peripheral field lines don't cross the gain region:

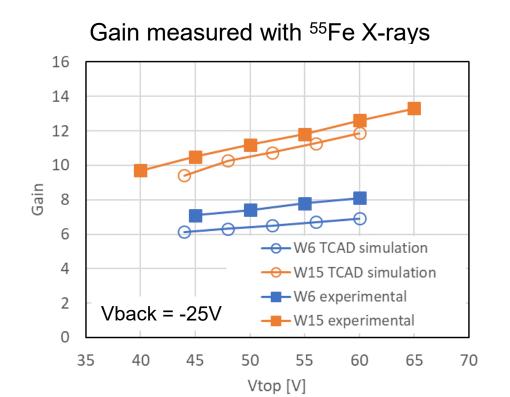
- «dead area» at the borders with gain 1
- better for timing uniformity

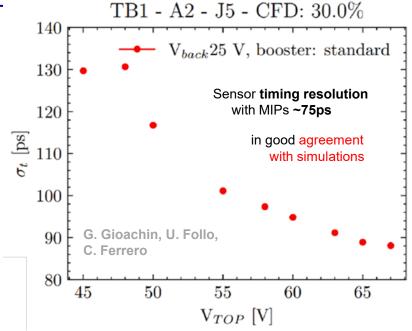


Layout A1

Layout A2

## Experimental results: gain and timing resolution



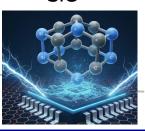


Fabrication run with thinner active layers and higher gain planned to further improve timing resolution

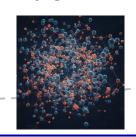




SiC



a:Si-H

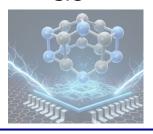


Ferroelectrics
NC-FETs

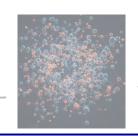




SiC



a:Si-H

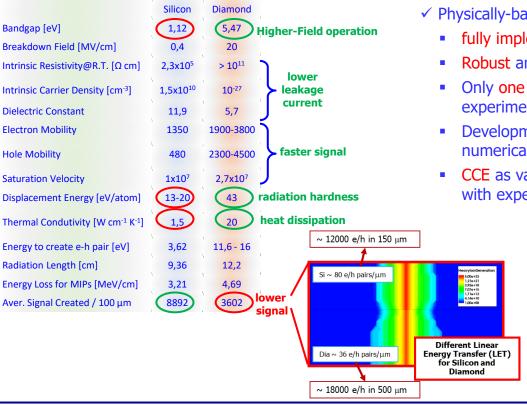


Ferroelectrics
NC-FETs



### CVD DIAMOND for particle detection applications

#### Silicon vs Diamond in **Electronics** (radiation detection)



✓ Physically-based numerical model of Diamond

- fully implemented within the TCAD environment.
- Robust and reusable simulation framework.
- Only one fitting parameter  $(N_T)$  to reproduce the experimental behavior of diamond.
- Development of a physically based diamond numerical model (deep-level traps).
- CCE as validation figure of merit (comparison with experimental data).

CVD diamond



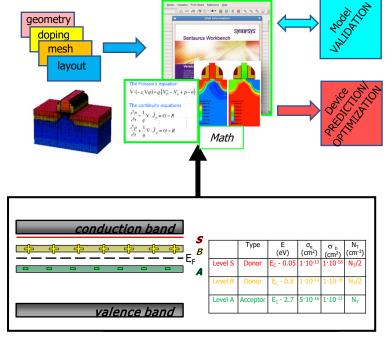


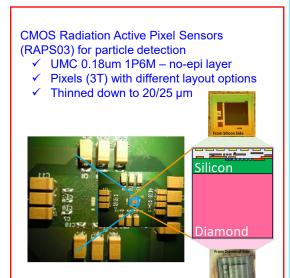
SEM images of a polycrystalline (pc) CVD diamond film: top view and cross section.

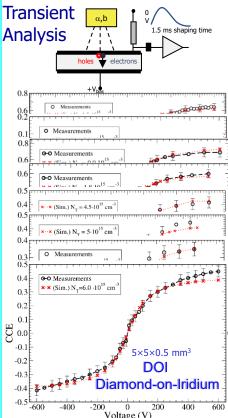


### TCAD modeling of CVD DIAMOND

✓ Innovative diamond modeling for DC, TV analyses within Synopsys<sup>©</sup> Sentaurus TCAD



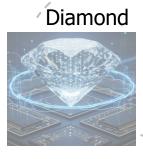




A. Morozzi et al., 13th Conference on Ph.D. Research in Microelectronics and Electronics (PRIME), pp. 73-76.

A. Morozzi et al., Materials Today: Proceedings, vol. 3, suppl. 2, 2016, pp. S153-S158, 2016.

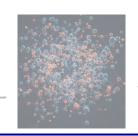
A. Morozzi et al., JINST, 11, C12043, 2016.



SiC



a:Si-H



Ferroelectrics
NC-FETs



### Modeling SiC devices within the TCAD environment



Philipp Gaggl

### Simulation setup

HiBPM Project Review Meeting

- Ouasi 1D simulation structure → fine mesh and fast simulation
- Adapted parameter file, strict convergence & error criteria [5]
- Assumed linear defect introduction with fluence and no intrinsic defects
- Initial parameters → Benchmark within the wide range of literature values Final parameters → Adapted to fit measurements

Defect	Туре	Energy [eV]	σ <sub>e</sub> [cm <sup>2</sup> ]	σ <sub>h</sub> [cm²]	
Ti	Acceptor	Ec – (0.11 – 0.23) [7, 9, 13, 17, 23, 27]	$3.0 \cdot 10^{-18} - 4.0 \cdot 10^{-13}$ [7, 9, 17, 23, 27]	2.0 · 10 <sup>-13</sup>	
Z <sub>1,2</sub>	Acceptor	E <sub>C</sub> - (0.5 - 0.7) [6, 7, 9-19, 23, 27, 32]	$\begin{array}{c} 1.0 \cdot 10^{\text{-}16} - 5.0 \cdot 10^{\text{-}10} \\ \text{[6, 7, 9-13, 15-18, 23, 27]} \end{array}$	$7.0 \cdot 10^{-15} - 1.0 \cdot 10^{-13}$ [13, 15, 17]	R
EH <sub>6,7</sub>	TBD Don.: [7, 15, 20, 29] Acc.: Rest	E <sub>C</sub> - (1.35 - 1.66) [6-8, 10, 11, 13-19, 21, 27, 32]	$\begin{array}{c} 2.0\cdot 10^{\text{-}18} - 9.0\cdot 10^{\text{-}12} \\ \text{[6-8, 10, 11, 14-18, 21, 27]} \end{array}$	1.0 · 10 <sup>-17</sup> – 1.0 · 10 <sup>-14</sup>	li v
$EH_4$	Acceptor	E <sub>C</sub> - (0.89 - 1.15) [6, 7, 10, 11, 16, 19-23]	$\begin{array}{l} 4.0\cdot 10^{\text{-}18} - 7.0\cdot 10^{\text{-}11} \\ \text{[6, 7, 10, 11, 16, 20, 21, 23]} \end{array}$	-	ir co
B-center	Donor	E <sub>V</sub> + (0.25 – 0.35) [10, 13, 23, 24, 26, 27, 32]	-	$1.0 \cdot 10^{-18} - 9.0 \cdot 10^{-11}$ [10, 13, 23, 27]	u
D-center	Donor	E <sub>V</sub> + (0.37 – 0.65) [13, 23, 24-27, 32]	$\begin{array}{c} 3.0 \cdot 10^{-19} - 8.0 \cdot 10^{-18} \\ {}_{[25]} \end{array}$	$\begin{array}{c} 5.0 \cdot 10^{-18} - 9.0 \cdot 10^{-12} \\ _{[23,  25,  27]} \end{array}$	

lange of iterature alues for nitially onsidered lefects

p++ - implant





high resistivity n-substrate

- 4H-SiC challenging
  - low charge carrier concentration
  - poor parameter values
- radiation damage modeled as traps
  - energy levels in the bandgap

Schematics of the quasi-1D simulation structure

n+ - buffer layer

HEPHY/OEAW

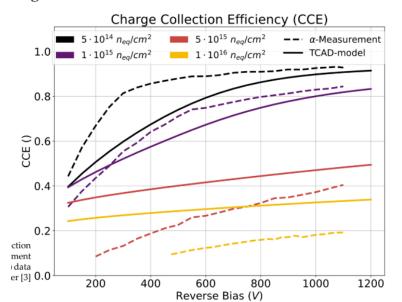
Material courtesy of T. Bergauer and Philipp Gaggl

### Simulation results

- ÖAW
  - AUSTRIAN ACADEMY OF



- Charge collection efficiency (CCE) under  $\alpha$ -irradiation [3]
- Experimental noise used as signal cut-off for simulated signals
- Very good agreement, especially for lower fluences
- Slow increase at low bias due to uniformly deposited energy in simulations



Charge collection measurement (α-particles) data from A. Gsponer [3]



Contact metal (Al, Ni, Ti) n - doped epi-layer ( $\approx 1.5 \cdot 10^{14}$  cm<sup>-3</sup>)

Amplification layer

High resistivity

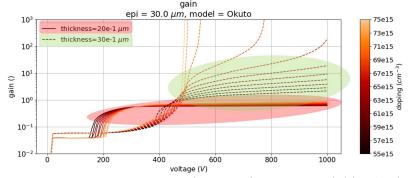
epitaxial layer (50 µm)

Buffer layer (1 µm) -Low quality substrate Design optimization.

Additional amplification (gain) layer

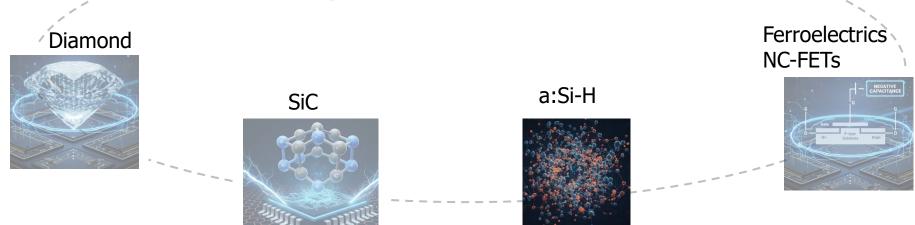
Benchmark simulations:

- Constant epi-doping of 1.5e14 cm<sup>-3</sup>
- ☐ Gain layer doping variation



Material courtesy of T. Bergauer and Philipp Gaggl





## Hydrogenated amorphous silicon (a-Si:H)

- Proposed as a suitable material to design thin a-Si:H detectors on flexible substrates (mostly Polyimide) for beam monitoring, neutron detection, and space applications.
  - intrinsic radiation tolerance, low cost, large area (different substrates, including flexible).
- Not included within the standard Synopsys TCAD material library
  - ☐ Development of a-Si:H parametric material model.
  - □ Different custom mobility models have been devised and implemented within the code as external PMI (Physical Model Interfaces) and accounting for different dependencies on temperature and internal potential distribution, thus resulting in a new mobility model embedded within the code.
  - ☐ Simple test structures, featuring p-i-n diodes have been simulated and compared to experimental data as a benchmark.

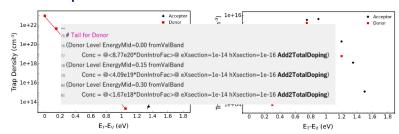




HASPIDE and 3D-SiAm INFN projects

### Modeling a-Si:H devices within the TCAD environment

- Not included within the standard material library
- Parameter file developed with all the characteristics
- Traps and validation of the model



Development of a user-defined PMI for the mobility

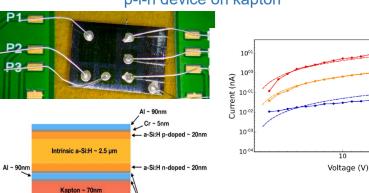
$$\mu = A^* V^m T^n exp\left(b\frac{\sqrt{|F|}}{T}\right)$$

#### HASPIDE



D. Passeri et al., Materials Science in Semiconductor Processing, 2024, 169, 107870

### p-i-n device on kapton



#### p-i-n device on crystalline Si D. Passeri et al.

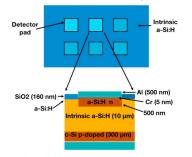
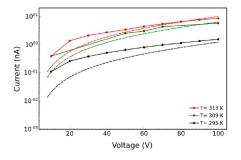


Fig. 10. p-i-n devices on crystalline silicon: simulated cross section.

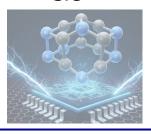


- T= 297 K

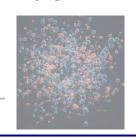
— T= 278 K



SiC



a:Si-H



Ferroelectrics
NC-FETs





Sub-threshold Swing (SS)

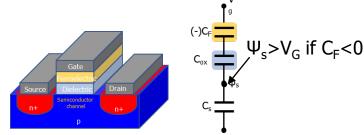
m>1





Development of High Energy Efficient Electronic Devices Based on Innovative

Ferroelectric Materials (HiEnD)



Body factor Transport factor

$$SS = \frac{\partial V_g}{\partial (\log I_d)} = \frac{\partial V_g}{\partial \psi_s} \times \frac{\partial \psi_s}{\partial (\log I_d)}$$

$$min\left(\frac{\partial \psi_s}{\partial (\log I_d)}\right) = \ln(10) \times \frac{k_B T}{q} \approx 60 \frac{mV}{decade}$$

$$\frac{\partial V_g}{\partial \psi_s} = 1 - \frac{C_s}{C_{ins}} (\alpha_f C_{ins} - 1) < 1$$

SS < 60 mV/decade typical of NC-FET

✓ The NegHEP project aims to investigate the radiation damage effects on Negative Capacitance Field Effect transistor

- ✓ Issues in low signal detection in thin layers:
  - ✓ minimum detectable signal is dominated by the switching threshold of a digital switch (e.g. ≈1 ke- for 28 nm technology, <100 e- for sub 10-nm technology).
  - ✓ Continuous increase in electronics performance demand
- ✓ Proposed solution: Negative capacitance (NC) FETs
  - ✓ By replacing the standard insulator with a ferroelectric insulator of the right thickness it should be possible to implement a step-up voltage transformer that will amplify the gate voltage thus enabling low voltage/low power operation.
- ✓ Would it be possible the concept of pixelated detector with sufficiently small cells to be read out entirely by simple inverters exploiting the NC "self-amplification"?

A. Morozzi, SIMDET 2025 – October 1, 2025

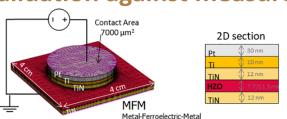


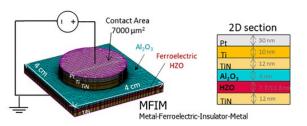


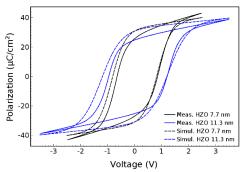


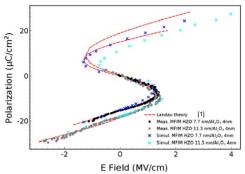


# Ferroelectric models: validation against measures









#### Preisach TCAD Model of hysteresis:

- ✓ remnant polarization Pr = 31 μC/cm²
- saturation polarization Ps = 33 μC/cm<sup>2</sup>
- ✓ coercive field Ec =1.1 MV/cm

for both 7.7 nm and 11.3 nm thin HZO films.

#### Structures:

- MFM (Metal-Ferroelectric-Metal)
  - tFE= 7.7 nm and 11.3 nm
- MFIM (Metal-Ferroelectric-Insulator-Metal)
  - tFE= 7.7 nm and 11.3 nm
  - tDE = 0-4 nm
- Fabricated on Si substrates with ferroelectric  $Hf_{0.5}Zr_{0.5}O_2$  (HZO) and dielectric  $Al_2O_3$  thin films.
- The experimental setup has been implemented within the TCAD environment.
- Hysteretic P-E trend was realistically accounted for by using the TCAD Preisach model of hysteresis.
- The Landau S-shaped plot was realistically accounted for by using GLK hysteresis-free model.

A. Morozzi et al., Solid-State Electronics Volume 194, August 2022, 108341.

A. Morozzi et al 2022 JINST 17 C01048.

A. Morozzi et al., 2021 EuroSOI-ULIS), Caen, France, 2021, pp. 1-4, doi: 10.1109/EuroSOI-ULIS53016.2021.9560683.

Morozzi, SIMDET 2025 – October 1, 2025





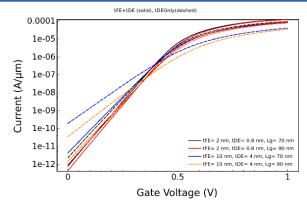


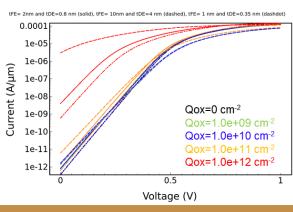


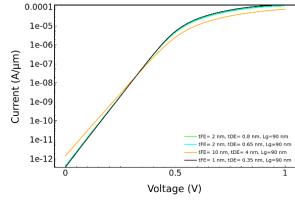
# Ferroelectric models: application NCFETs

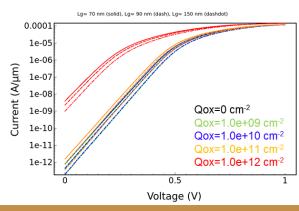
- ☐ Guidelines for the optimization of the NC-FETs design.
- Capacitance matching |C<sub>FE</sub>|< C<sub>DE</sub> for the reduction of the Sub-threshold slope.











Morozzi, SIMDET 2025 – October 1, 2025

### Combining TCAD and Allpix Squared



- → Allpix² is a versatile, open-source simulation framework for silicon pixel detectors.
- TCAD is crucial for understanding the fabrication process and electrical characteristics of semiconductor devices, Allpix Squared complements this by providing insights into how these devices respond to particle interactions (detailed energy deposition) and the response of pixel detectors..
- □ The combination of these tools enables a more holistic approach to semiconductor device design, optimization, and analysis.
- Detailed E Field maps are imported from TCAD simulations to drastically improve the precision of a sensor simulation.

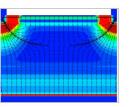
## Sentaurus TCAD Syllicon to Software Technology Computer-Aided Design

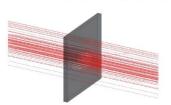
- ★ Model semiconductor devices by means of finite element analysis
- ★ Electric Fields: accurate and realistic

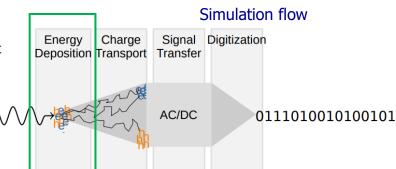




- ★ Simulate full response of semiconductor detector
- ★ Particle Events: fast and high statistics







A. Simancas et al., 4th Allpix Squared Workshop (2023)

detector

readout

### Conclusion

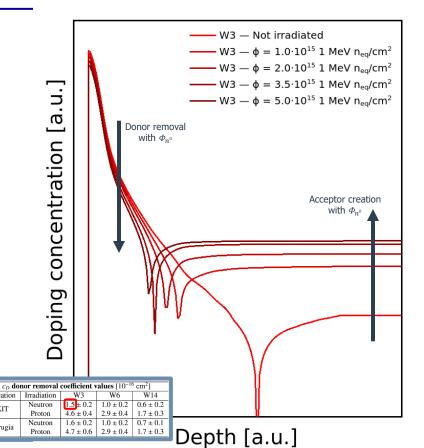
- ✓ Synopsys Sentaurus TCAD powerful tool to accelerate innovation and drive the industry forward.
- ✓ Sentaurus TCAD's versatility makes it suitable for a wide range of applications.
- ✓ TCAD plays a pivotal role in the design/optimization of rad-hard devices
  - Modelling radiation damage effects is a tough task!
  - New guidelines for future production of radiation-resistant options.
  - Modeling dopant removals, impact ionization, carriers' mobility, trap dynamics
  - Every device needs specific defect modeling (LGADs for example, prone to acceptor removal)

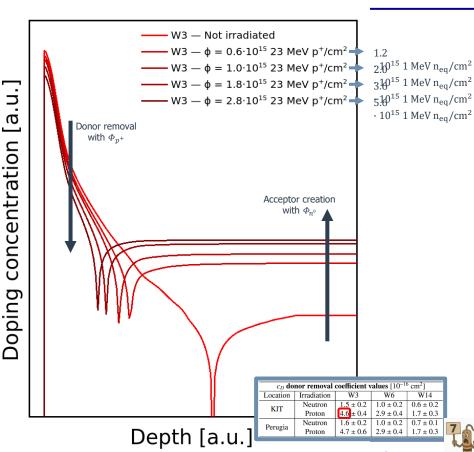




### RSD2 NPLUS W3 — Neutron

### **Proton**





Location

Perugia

### TCAD simulation of LGAD devices

#### ✓ Physical models

- Generation/Recombination rate
  - Shockley-Read-Hall, Band-To-Band Tunneling, Auger
  - Avalanche Generation => impact ionization models, van Overstraeten-de Man, Okuto-Crowell, Massey<sup>[1]</sup>, UniBo
- Fermi-Dirac statistics
- Carriers mobility variation doping and field-dependent
- Physical parameters
  - e-/h+ recombination lifetime

#### ✓ Radiation damage models: "PerugiaModDoping"

- "New University of Perugia model"
  - Combined surface and bulk TCAD damage modeling scheme<sup>[2]</sup>
  - Traps generation mechanism
- Acceptor removal mechanism =>  $N_{GL}(\phi) = N_A(0)e^{-c\phi}$ 
  - where
    - Gain Layer (GL), c removal rate (Torino parameterization<sup>[3]</sup>)
- Acceptor creation

$$N_{A,bulk} = \begin{cases} N_{A,bulk}(0) + g_c \phi, & 0 < \phi < 3E15 \ n_{eq}/cm^2 \\ 4.17E13 \cdot \ln(\phi) - 1.41E15, & \phi > 3E15 \ n_{eq}/cm^2 \end{cases}$$

where  $g_c = 0.0237 \text{ cm}^{-1}$  (**Torino acceptor creation**)

- [1] M. Mandurrino et al., IEEE NSSMIC 2017.
- [2] D. Passeri, AIDA2020 report, CERN Document Server.
- [3] M. Ferrero et al., <a href="https://doi.org/10.1016/j.nima.2018.11.121">https://doi.org/10.1016/j.nima.2018.11.121</a>. Sola et al., <a href="https://doi.org/10.1016/j.nima.2018.07.060">https://doi.org/10.1016/j.nima.2018.07.060</a>.

#### Surface damage $(+ Q_{OX})$

Туре	Energy (eV)	Band width (eV)	Conc. (cm <sup>-2</sup> )
Acceptor	$E_C \le E_T \le E_C - 0.56$	0.56	$D_{IT} = D_{IT}(\Phi)$
Donor	$E_V \le E_T \le E_V + 0.6$	0.60	$D_{IT} = D_{IT}(\Phi)$

1e-8

#### Bulk damage

Туре	Energy (eV)	η (cm <sup>-1</sup> )	σ <sub>n</sub> (cm²)	σ <sub>h</sub> (cm²)
Donor	E <sub>c</sub> - 0.23	0.006	2.3×10 <sup>-14</sup>	2.3×10 <sup>-15</sup>
Acceptor	E <sub>c</sub> - 0.42	1.6	1×10 <sup>-15</sup>	1×10 <sup>-14</sup>
Acceptor	E <sub>c</sub> - 0.46	0.9	7×10 <sup>-14</sup>	7×10 <sup>-13</sup>

## RSD2 batch — NF

